

ABSTRACT

SUBSTRATE CLEANING APPARATUS AND CLEANING METHOD OF SUBSTRATE

A substrate cleaning apparatus has: a substrate rotating part 110 that rotates a substrate W; an edge cleaning member 10 for cleaning an edge part of the substrate W; an edge rotating part 40 that rotates the edge cleaning member 10 around an edge rotary shaft 19 that extends in a direction orthogonal to a substrate rotary shaft 130; a moving part 31, 36 that moves a position of the edge cleaning member 10 with respect to the edge part of the substrate W; and a control part 50 that controls the moving part 31, 36 to move the position of the edge cleaning member 10 with respect to the edge part of the substrate W, and causes the edge cleaning member 10 to clean a one-side edge area W1 including a face on one side, a side face area W3 including a side face, and an another-side edge area W2 including a face on another side in the edge part of the substrate.

Figure 3